

Plasma Surface Ion Energy Analyser





Multi-Grid Retarding Field Energy Analyser Substrate Mounted RFEA Placed on a Grounded or Biased Surface



The Semion 800™ is a precision plasma measurement instrument used in a large number of plasma laboratory applications. The Semion 800™ is the key instrument used by scientists to measure the ion energy and flux arriving at a surface in a plasma process chamber.

The Semion 800[™] can be placed on a biased or grounded surface. Among the key parameters measured are Ion Energy, Ion Flux, Electron Energy, Plasma Potential and Floating Potential. The Semion 800[™] provides plasma parameter measurement in DC, RF, Microwave, Continuous and Pulsed plasma. The Semion 800[™] is the most advanced and trusted, fully automated retarding field energy analyser on the market.

The Semion 800™ helps the user to understand ion surface interactions and the ions impact on surface treatment. The Semion 800™ is an essential plasma process diagnostic to understand the correlation between plasma inputs and the plasma state. The Semion 800™ reduces process and tool development time, as well as the time to market for new plasma products. Pulsed plasmas are used to tailor the electron or ion energy and The Semion 800™ is an integral part of such process development.



Key Indicators

Substrate mounted Retarding Field Energy Analyser Probe

- In-situ measurement of:
 - Ion Energy Distribution
 - Ion Flux
 - Ion Current
 - Electron Flux and Energy
- Measurement of Ion Energies up to 800eV at pressures up to 300mT
- Easy to install, no chamber retrofit required
- Portable system allowing analysis in multiple chambers using single system

Benefits

- Robust and Easy to Install
- Easy to Use Software
- Real Time Measurements
- Replaceable Sensors
- Sensor holder sits on a bias or grounded surface
- Fully automated software analysis
- Custom holder materials available







Specifications

Semion 800	
Ion Energy Range	0 to 800eV*
Ion Current	2mA DC max
Ion Flux	0.1 - 20mA/cm ²
IEDF Resolution	± 1eV nominal

^{*}dependant on DC bias

RFEA Probe				
Probe Configuration	3-grid			
Button Probe Diameter	33mm			
Holder Diameter	70mm, 100mm (4"), 300mm (12") as standard			
Holder Thickness	5mm			
Max Operating Temperature	200°C			
Mounting	RFEA Probe holder mounted on electrode			
Probe Enclosure Material	Aluminium, anodized, stainless steel & Al2O3			
Probe Holder Material	Aluminium, anodized aluminium, stainless steel, Al2O3			
RFEA Probe Cable Length	650mm standard (custom available)			

Feed-through Assembly					
Flange type	KF40 standard, CF40				
Control Unit Electronics					
Voltage Range -600V to +600V (suppression voltage),					
	-420V to +420V (grid voltages),				
Current range	100pA to 2.4mA				
Connectivity	USB 2.0				

Application Software	
Operating System	Windows 2000/XP/Vista/Windows 7 Compatible





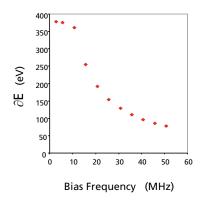
Product Operating Parameter Table

High	> 10 ⁵ Pa	>760 Torr	> 5000°	> 10 ¹⁴ cm ⁻³	SiH ₄	Microwave (3 GHz - 20 GHz)	> 100 KeV
	1000Pa - 10⁵Pa	10 - 760 Torr	5000°	10 ¹² - 10 ¹⁴ cm ⁻³	C4F ₈ , SF ₆	Microwave (1 GHz - 3 GHz)	10 - 100 KeV
	100Pa - 1000Pa	1 - 10 Torr	1000°	10 ¹⁰ - 10 ¹² cm ⁻³	CHF ₃	UHF (100 MHz - 1 GHz)	2500 - 10,000 eV
Medium	10Pa - 100Pa	0.1 - 1 Torr	500°	10 ⁸ - 10 ¹⁰ cm ⁻³	Cl	RF (1 MHz - 100 MHz)	800 - 2,500 eV
	1Pa - 10Pa	10 - 100 mTorr	200°	10 ⁶ - 10 ⁸ cm ⁻³	O ₂	MF (0 - 1 MHz)	400 - 800 eV
	0.1Pa -1Pa	1 - 10 mTorr	100°	10 ⁴ -10 ⁶ cm ⁻³	N ₂	pDC (0 - 350 kHz)	100 - 400 eV
Low	< 0.1 Pa	< 1 mTorr	20°	< 10 ⁴ cm ⁻³	Ar, He	DC (0 kHz)	0 - 100 eV
	Pressure (Pascal)	Pressure (Torr)	Gas Temperature	Density	Gas Reactivity	Power Frequency	Ion Energy

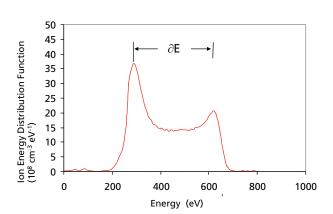
System Operating Parameters Beyond Operating Parameters

Graphical Data

Measurement of ∂E as function of bias frequency



Ion Energy Distribution Function on a RF Biased Substrate using Semion 800



Product Dimensions

